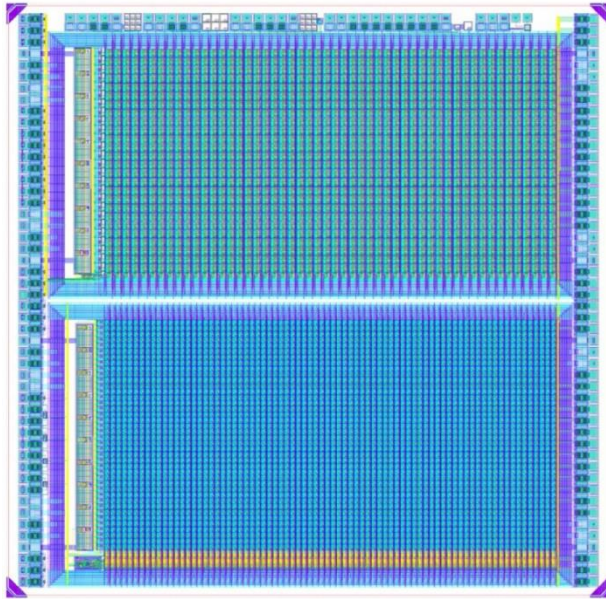
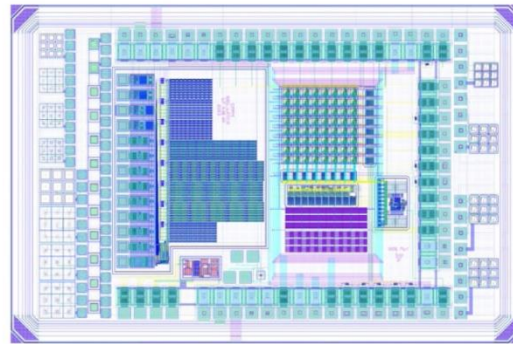


RD50-MPWx chip series

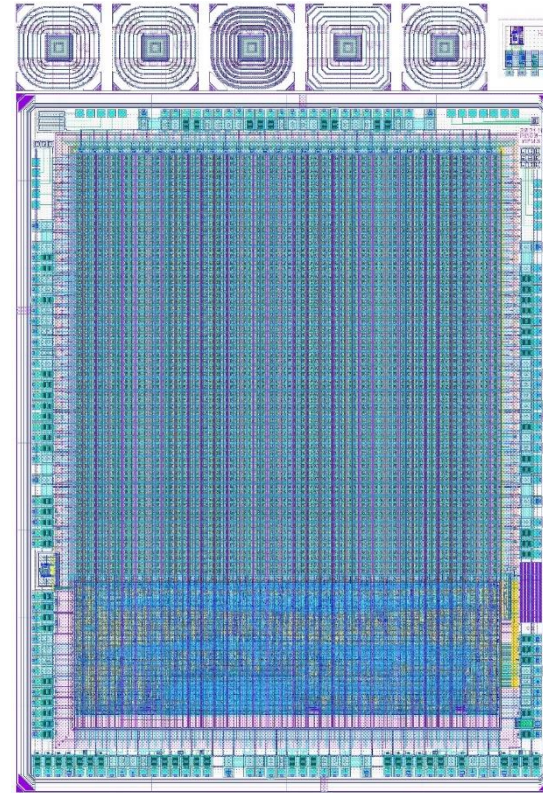
RD50-MPW1



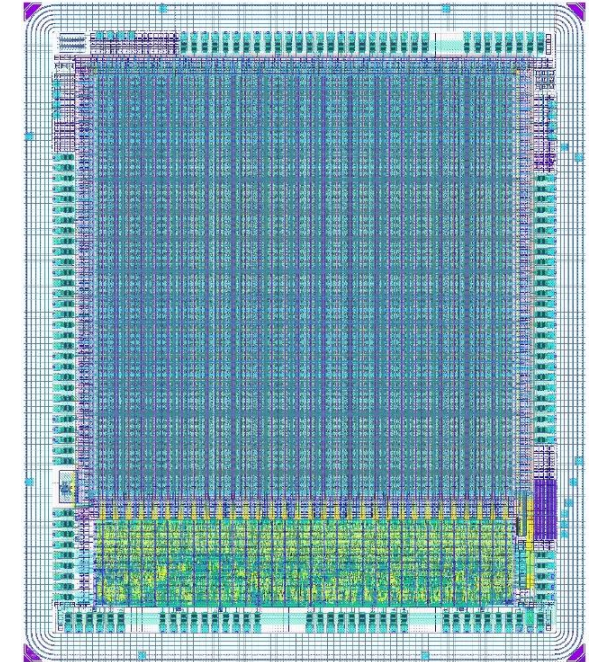
RD50-MPW2



RD50-MPW3



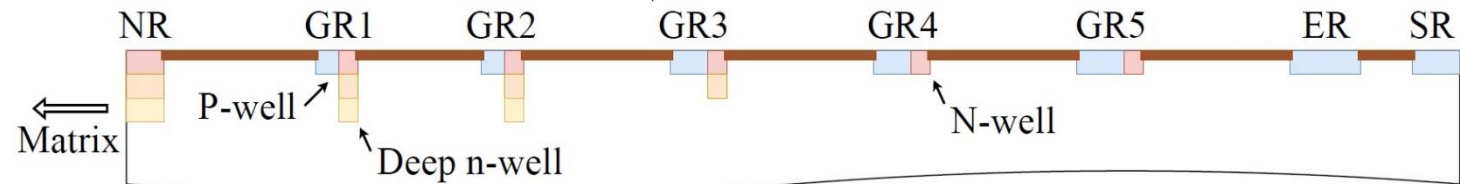
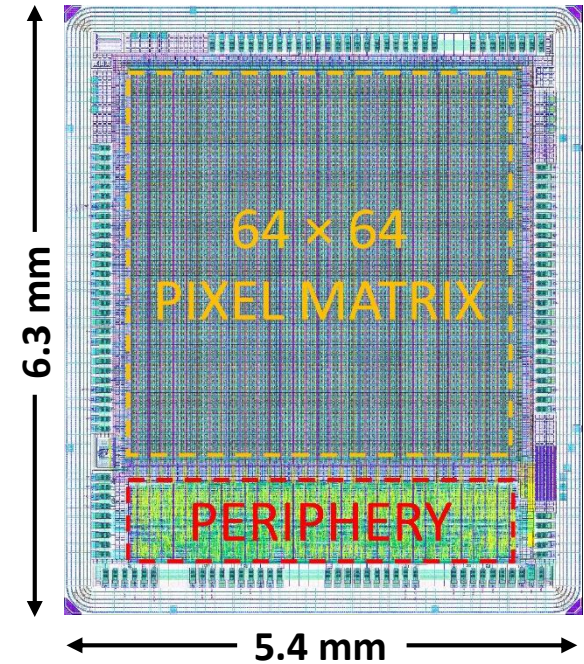
RD50-MPW4



RD50-MPW4 (common project 2023-02)

■ Main goals

- To further improve the current-to-voltage-characteristics
 - Much higher V_{BD} (and much higher radiation tolerance)
 - New chip ring frame (test structure in RD50-MPW3)
 - Chip substrate biasing with topside edge contacts or backside contacts
- To achieve low-noise by separating the digital in-pixel and digital peripheral power and ground domains
- To reduce the size of the digital periphery
- To fix small design bugs



■ Chip contents

- Matrix of depleted CMOS pixels with FE-I3 style readout
- Tests structures (e-TCT, DLTS)
- Fabricated on standard and 3k $\Omega \cdot \text{cm}$ wafers
- Backside biasing is possible

To be delivered very soon... stay tuned!

RD50-MPW4 (common project 2023-02)

- We expect to receive topside biased samples before the end of the year...
- and backside biased samples some time in the new year
- The production of the chip carrier board is ongoing, and we think it will be ready to start measuring the chip once this is delivered
- We have requested beam time in spring at DESY
 - If people want to contribute with lab measurements
 - Or join our test beam campaign(s)
 - Please get in touch!